RF-2.75 Plasma Source

Description

- The RF-2.75 Compact RF Plasma Source is excellent for oxide and nitride deposition.
- The RF Plasma Source and manually tuned RF matching network mounts to a standard 2.75" CF (70 mm) Flange.
- Equipped with an optical viewport, the RF-2.75 Plasma Source is fully compatible with SVT Associates’ RoboRF Automation Software.
- The integrated charge suppression ensures that ions do not reach the target and also eliminates substrate damage due to unintentional sputtering.

Features

- Compact Design
- Integrated Charge Suppression
- Automatic Tuning Network Available
- Optical Port for Plasma Monitoring
- Integral Water Cooling
- Custom Plasma Chamber and Aperture Available

Specifications

<table>
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<th>Models</th>
<th>Description</th>
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<tr>
<td>SVTA-RF-2.75PBN</td>
<td>PBN, 0.11&quot; Aperture</td>
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<tr>
<td>SVTA-RF-2.75ALO</td>
<td>Alumina, 0.11&quot; Aperture</td>
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<td>SVTA-RF-2.75Q</td>
<td>Quartz, 0.11&quot; Aperture</td>
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RF Power Level: 150 – 400 Watts
Gas Flow Rate: 0.1 – 5 SCCM
Flange: 2.75" CF
Source Diameter: 1.30"
Water Cooling: 0.17 GPM Flow Rate
RF Matching Network: Manually Tuned
Plasma Chamber: PBN, Alumina, or Quartz

Nitrogen Plasma Emission Spectra of the SVTA-RF-2.75 Plasma Source